

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicant:

Bradley F. Bowden

Kenneth E. Hrdina

Serial No:

10/085,838

Filed:

February 27, 2002

For:

DRY PRESSING OF SPRAY DRIED SOOT

TO MAKE EUV COMPONENTS

INFORMATION DISCLOSURE STATEMENT UNDER 37 C.F.R. §§ 1.56, 1.97 – 1.98

Asst. Commissioner of Patents and Trademarks Washington, DC 20231

Dear Sir:

The Examiner's attention is hereby directed to the following reference(s) listed on the attached Form PTO-1449 for consideration in connection with the examination of the above-identified patent application. One copy of the reference(s) is enclosed.

This submission does not represent that a search has been made or that no better art exists and does not constitute an admission that each or all of the enclosed documents constitute "prior art." If it should be determined that any of the submitted documents do not constitute "prior art" under United States law, applicant(s) reserve the right to present to the office the relevant facts and law regarding the appropriate status of such documents.

Applicant(s) further reserve the right to take appropriate action to establish the patentability of the disclosed invention over the enclosed references, should one or more of the references be applied against the claims of the present application.

Respectfully submitted,

Timbthy\M. Schaeberle Registration No. 34,424 Corning Incorporated

SP-TI-03-1

Corning, NY 14831

(607) 974-3/164/

Date:

CERTIFICATE OF MAILING

Examiner: To Be Assis

Group Art Unit: 1731

I hereby certify that this correspondence is being deposited with the United States Postal Service as first class mail in an envelope addressed to Asst. Commissioner of Patents and Trademarks, Washington, D.C. 20231

Signature: Colleen E. Doherty

Revision: March 7, 2000

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OTHER ART (Including Author, Title, Date, Pertinent Pages, etc.)  A1 P. Shultz & H. Smith, Ultra-Low-Expansion Glasses and Their Structure in the SiO	<b>ر</b>
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OTHER ART (Including Author, Title, Date, Pertinent Pages, etc.)	<b>)</b>
A1 P. Shultz & H. Smith, Ultra-Low-Expansion Glasses and Their Structure in the SiO	<del></del>
1 102 System, Amorphous Materials, papers presented to the Third International	*
Conference on the Physics of Non-Crystalline Solids, held at Sheffield University	-
A2 George H. Beall, Industrial Applications iof Silica, Reviews in Mineralogy, Vol. 29	.)
(Sinca), (1994), 409-303.	
A3 Charles Gwyn et al., Extreme Ultraviolet Lithography, November 1999, 97-141.	<del></del>
A4   EUV Lithography NGL Technology Review, June 9, 1999, Chicago, Illinois	
A3   Charles Gwyn et al., Extreme Ultraviolet Lithography 1-6	
Ab William M. Tong et al., Substrates Requirements For Extreme Litraviolet Lithogram	ohv.
Information Science & Technology, Lawrence Livermore National Laboratory	,,,,
A7 O.V. Mazurin et al., Crystallizaiton of Silica and Titanium Oxide-Silica Corning	
Ulasses (Codes /940 & /9/1), Journal of Non-Crystalline Solids 18 (1975) 1.0	
As ISIMOTO CO. LTD., Purity and Chemical Reactivity	<del></del>
http://www.isimoto.com/isimoto/english/feature1.html, 1-3, 5/17/99  A9 ISIMOTO CO. LTD. Product Information	
	<u>-</u>
http://www.isimoto.com/isimoto/english/product_info.html, 1-4, 5/17/99  A10 Rapid Prototyping http://mtiac_jitri_org/pubs/rp/rp1_html	
ATO   Rapid Prototyping, http://mtiac.iitri.org/pubs/rp/rp1 htm	
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http://www.3dsystems.com/products/slssystems/vanguard/index.asp?promo= A12   Corning, Semiconductor Materials LUE Zoro Europsian Cl	= ,
A12   Coming, Semiconductor Materials ULE Zero Expansion Glass	
http://www.corning.com/semiconductormaterials/products_services/ule.asp	
The state of Augustine Utilaviolet Littlegraphy IEEE Journal of Augustine	1
Electronics, Vol. 35, No. 5, May 1999, 694-699.	_

EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609: draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.

DATE CONSIDERED:

**EXAMINER:** 

N 1 9 2002 ECRM PTO-1449 (MODIFIED)

LIST OF PATENTS AND
PUBLICATIONS
R APPLICANTS INFORMATION
DISCLOSURE STATEMENT

ATTORNEY DOCKET NO.

SP01-329

SERIAL NO.

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APPLICANT Bowden et al.

FILING DATE February 27, 2002

GROUP: 1731

REFERENCE DESIGNATION

U.S. PATENT D	OCHMENITS
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	1	T	<del></del>	B. TATENT DOCUME	<u>2N1S</u>		
Examiner Initial		Document Number	Date	Name	Class	Sub-	Filing Date if Approp.
	AA	2,326,058	8/3/43	Nordberg	100	Class	<b>_</b>
	AB	4,501,602	2/26/85	Miller et al.		52	
	AC	<del></del>			65	18.2	
		5,043,002	8/27/91	Dobbins et al.	65	3.12	<del>                                     </del>
	AD	5,152,819	10/6/92	Blackwell et al.	65	3.12	<del> </del>
	AE	5,154,744	10/13/92	Blackwell et al.	65	+	<del> </del>
	AF	5,686,728	11/11/97	Shafer		3.12	
	AG	5,970,751		<del> </del>	250	492.2	
		<del></del>	10/26/99	Maxon et al.	65	414	
	AH	6,013,399	1/11/00	Nguyen	430	<del></del>	L
	ΑI	6,299,318	10/9/01	Braat		5	
		<del>'</del>	10/2/01	Diaat	359	856	

## FOREIGN PATENT DOCUMENTS

	Document Number	Date	Country	Class	Sub-	Trans	slation
AJ	WO 01/07967·	2/1/01	PCT	0000	Class	Yes	No
 AK	WO 01/08163*	2/1/01		G03C	5/00	X	<u></u>
 AL	WO 01/08103*		PCT	G21K	5/00	X	
 AM		10/11/01	PCT PCT	G03F	1/14	X	
 1	WO 00/48775	8/24/00	PCT	B23B	T	X	
 AN	WO 02/32622•	4/25/02	PCT	B24B	7/24	$\frac{X}{X}$	
 AO	WO 02/26647 ·	4/4/02	PCT	C03B	+		
 AP	WO 02/32616 ·	4/25/02	PCT		37/016	X	
 AO	EP 0 903 605A2	3/24/99		B23P	13/04		
AR	EP 1 106 582A2		EPO	G02B	13/14	X	
 7111	LI 1 100 382AZ	6/13/01	EPO	C03B	19/10	X	

**EXAMINER:** 

## DATE CONSIDERED:

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